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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:

Leonard C. Pipes et al.

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Art Unit: 2812

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Examiner: Stanetta D. Isaac

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Atty Docket: ITL.0851D1US
P15016D

§

Assignee: Intel Corporation

Serial No.: 10/764,751

Filed: January 26, 2004

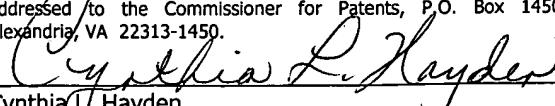
For: Implanting Ions in Shallow
Trench Isolation Structures

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY TO FINAL REJECTION

Sir:

In response to the final rejection mailed August 10, 2005, please amend the above-referenced patent application as follows:

Date of Deposit: <u>August 26, 2005</u>
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Cynthia L. Hayden